EAST Search History

Ref #	Hits	Search Query	DBs	Default Operator	Plurals	Time Stamp
L1	9	("205"/$.ccls. "204"/$.ccls.) and surface near3 roughness and (electropolish$3 cmp (electrochemical mechanical chemical) adj5 polish$3) and (conductive adj4 (trace)) and ((board printed) near4 circuit)	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2006/03/01 10:23
L2	0	("205"/$.ccls. "204"/$.ccls.) and (electropolish$3 cmp (electrochemical mechanical chemical) adj5 polish$3) and (conductive adj4 (trace)) with roughness and ((board printed) near4 circuit) not l1	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2006/03/01 10:24
L3	0	(electropolish$3 cmp (electrochemical mechanical chemical) adj5 polish$3) and (conductive adj4 (trace)) with roughness and ((board printed) near4 circuit) not l1	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2006/03/01 10:25
L4	0	(electropolish$3 cmp (electrochemical mechanical chemical) adj5 polish$3) and (conduct$4 adj4 (trace)) with roughness and ((board printed) near4 circuit) not l1	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2006/03/01 10:25
L5	0	(electropolish$3 cmp (electrochemical mechanical chemical) adj5 polish$3) and (conduct$4 adj4 (trace)) same roughness and ((board printed) near4 circuit) not l1	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2006/03/01 10:25
L6	100	(electropolish$3 cmp (electrochemical mechanical chemical) adj5 polish$3) and (conduct$4 (trace)) same roughness and ((board printed) near4 circuit) not l1	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2006/03/01 11:18
L7	44	(electropolish$3 cmp (electrochemical mechanical chemical) adj5 polish$3) and (conduct$4 (trace)) with roughness and ((board printed) near4 circuit) not l1	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2006/03/01 10:29

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L8	10	(electropolish$3 cmp (electrochemical mechanical chemical) adj5 polish$3) same ((conduct$4 trace) with roughness) and ((board printed) near4 circuit) not l1	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2006/03/01 10:27
L9	80	(electropolish$3 cmp (electrochemical mechanical chemical) adj5 polish$3) and (wire line) same roughness and ((board printed) near4 circuit) not l1	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2006/03/01 11:23
L10	70	(electropolish$3 cmp (electrochemical mechanical) adj5 polish$3) and (wire line) same roughness and ((board printed) near4 circuit) not l1	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2006/03/01 11:23